

Reaction mechanisms in DeNO_x by activated ammonia generated by DBD

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Abstract— A unique SNCR system by activated ammonia injection using an intermittent dielectric barrier discharge (DBD) has been developed to remove NO_x from an incinerator. However, the NO_x reduction mechanisms are not elucidated so far. In this paper, chemical species in the activated ammonia was investigated at the DBD reactor exit. Hydrogen was detected as main composition of the activated ammonia. The simulation gas of the activated ammonia (NH₃+H₂) was prepared to be clear the contribution of hydrogen, and the deNO_x performance of the simulation gas was examined. It found that hydrogen has the role of enlargement of temperature window in deNO_x reaction. DeNO_x mechanisms were concerned using elementary reaction analysis based on Miller & Bowman mechanism. It was clear that formation of HNO and NH from hydrogen in the activated ammonia promoted deNO_x reaction at low temperature region.

Keywords—Dielectric barrier discharge, nitrogen oxide, DeNO_x, ammonia, hydrogen.

I. INTRODUCTION

Because an environmental problem came to attract attention, emission concentration regulation of NO_x by local agreements came to be determined in smaller combustion facilities which was thus far left out of emission concentration regulation of NO_x. A method to remove NO_x is adopted generally by a combustion control and Selective Catalytic Reduction systems (SCR) in the combustion facilities of business use or the industrial use. But the practical use of a small and economical denitrification device is expected in smaller combustion facilities from a point of view such as a setting area and the driving cost.

However, DeNO_x reaction temperature range for SNCR is very high temperature range from 850 °C to 1175 °C (hereinafter referred to as Temperature window) [1]. Since it is not possible to secure a sufficient reaction time at Temperature window, Decrease of NO_x removal efficiency is a problem to smaller combustion facilities. It is necessary to technology to lower Temperature window in order to solve the problem.

The authors discovered that the Temperature window is 150-200 °C extended to the low-temperature side to inject excited NH₃ gas by atmospheric pressure plasma into the combustion exhaust gas (hereinafter referred to as Radical Injection Method). We have studied experimentally the effect of various reaction parameters such as NH₃/NO molar ratio and input power on the NO_x removal efficiency along the way [2] – [4]. However, it is not possible to elucidate the denitration reaction mechanism by radical injection method.

In order to clarify the denitration reaction mechanism of radical injection method, It is necessary to clarify quantitatively the product that excited NH₃ by atmospheric pressure plasma. In this paper, we quantified the composition of stable species (NH₃, H₂, and N₂) in excited ammonia by atmospheric pressure plasma and discussed the reaction mechanism of Radical Injection Method by comparing the denitrification property.

II. METHODOLOGY

Figure 1 shows a schematic diagram of the ammonia radical injection De-NO_x system test facility using the pulsed DBD. The facilities contains two gold furnaces with quartz tubes for controlling gas temperature, simulant gas (NO/N₂/O₂) supply system, Simultaneous NO_x removal gas (NH₃/Ar) supply system, plasma reactor, high voltage pulsed power supply, three gas analyzer (NO_x, N₂O and O₂), Micro GC and photo acoustic spectroscopy (PAS). Plasma reactor is double-tube structure cylinder made from SiO₂. Plasma reactor size is as below. Outside diameter of outside tube is 61 mm (thickness 2mm), outside diameter of inside tube is 54 mm (thickness 2mm), length is 490 mm and gap between outside tube and inside tube is 1.5 mm. High voltage electrode (SUS316) is placed in inside of inner-tube and punched metal (SUS316) is looped around outer-tube as ground electrode. Length of ground electrode is 360 mm. Electrical properties of the plasma reactor are described in past paper [2].

An NH₃/Ar mixture gas was supplied to gap section of plasma reactor. In the plasma reactor, NH₃ were excited by atmospheric pressure plasma generated by using a dielectric barrier discharge. Excited NH₃ was sampled at plasma reactor outlet. NH₃ concentration in the sample gas was measured by PAS, H₂ and N₂ concentrations were measured by Micro-GC.

On the other hand, simulated exhaust gas (NO/O₂/N₂) was supplied to pre-heating tube (Length 500mm) and pre-heated to 500 °C. Simulated exhaust gas and excited NH₃ were mixed in mixing chamber, supplied to reaction tube (Length 600mm). NO_x removal efficiency was calculated from outlet gas composition each of reaction temperature (500 °C - 800 °C). Gas composition of outlet gas is measured continuously by each gas analyzer.

Table 1 shows experimental conditions. We researched effect of NH₃/Ar flow rate and applied voltage for composition change of excited NH₃ and effect of applied voltage and reaction temperature for NO_x removal efficiency.

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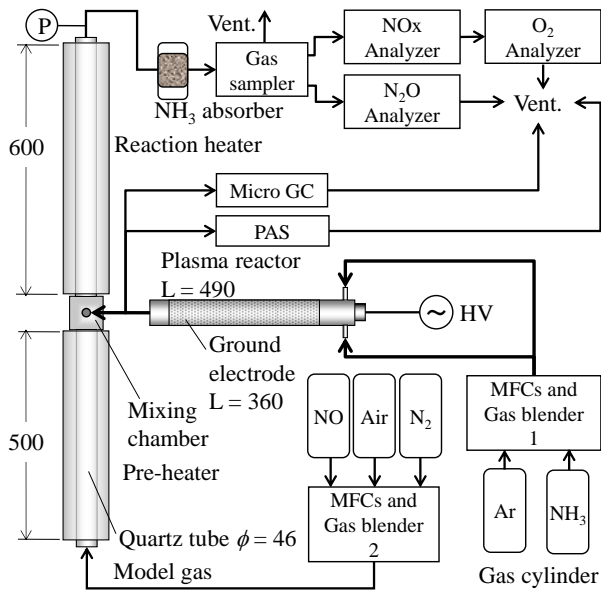


Fig.1 Schematic diagrams of experimental apparatus.

Table 1 Experimental conditions.

Measurements of chemical composition	
NH ₃ /Ar gas mixture	0.2, 0.4, 0.8 L/min*
Applied voltage	0–15 kV
Repetition rate	10 kHz
Initial NH ₃ concentration	4840 ppm
DeNOx experiments	
NH ₃ /Ar gas mixture	0.8 L/min*
NO/O ₂ /N ₂ gas mixture	2.2 L/min*
Initial NO concentration	500 ppm
Initial O ₂ concentration	8.3 %
Temperature	500–800°C

*Standard conditions (293 K and 0.1 MPa).

III. RESULTS & DISCUSSION

A. Chemical composition of excited NH₃

Figure 2 shows variation in NH₃ decomposition as functions of applied voltage and flow rate of NH₃/Ar gas. NH₃ decomposition is calculated according to the following equation.

$$D_{\text{NH}_3} = ([\text{NH}_3]_1 - [\text{NH}_3]_0) / [\text{NH}_3]_1 \times 100. \quad (1)$$

Where $[\text{NH}_3]_1$ is initial concentration of NH₃ at plasma reactor inlet, $[\text{NH}_3]_0$ is concentration of NH₃ at plasma reactor outlet.

NH₃ decomposition increases with the increasing applied voltage and the decreasing flow rate of NH₃/Ar gas. The factor of NH₃ decomposition is considered that NH₃ get higher energy than bond enthalpy ($450\text{kJ}\cdot\text{mol}^{-1}$) of NH₃ from electric energy of Ar plasma. The increasing of NH₃ decomposition is explained that electric energy to NH₃ increased by the increasing applied voltage and the decreasing NH₃/Ar gas flow rate. NH₃ is decomposed

completely at gas flow rate 0.2L/min and applied voltage 15kV.

Figure 3 shows chemical composition (H₂, N₂, and unreacted NH₃) in plasma reactor outlet gas at each applied voltage. NH₃ concentration decreases with the increasing applied voltage, but H₂ and N₂ concentrations increases. It was found that unknown substance is contained in excited NH₃ gas. The unknown substance is considered stable NmHn compound.

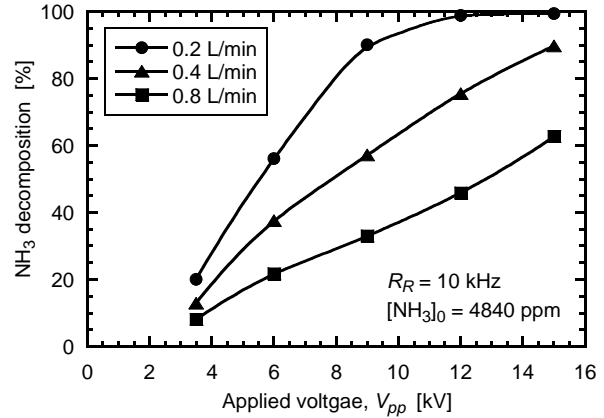


Fig.2 Variation in NH₃ decomposition as functions of applied voltage and flow rate of NH₃/Ar gas.

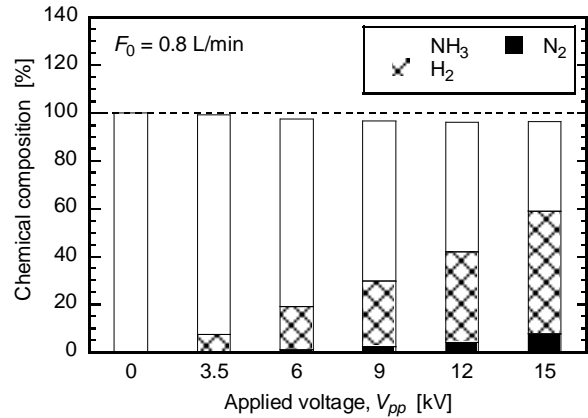


Fig.3 Gas composition of activated ammonia at the plasma reactor exit at NH₃/Ar flow rate of 0.8 L/min.

B. NOx removal characteristics by excited NH₃ gas

It was found that the components of excited NH₃ are H₂ and unreacted NH₃ mainly from Fig.3. Lyon et al. shows that Temperature window shifts about 150 °C to lower temperature side [5]. Moreover, Muzio et al. shows that H₂/NO molar ratio to obtain maximum NOx removal varies according to reaction temperature and NH₃/NO molar ratio in addition to show similar findings to Lyon et al. [6]. In other words, it is highly possible that H₂ generated from the ammonia excited by atmospheric pressure plasma contribute to the expansion of Temperature window. Therefore, we prepares simulant excited NH₃ gas (NH₃ + H₂) according to Fig.3 and performs NOx removal experiments that injects simulant excited NH₃ gas to Mixing Chamber (Fig.1) directly. Figure 4 shows comparison of deNOx characteristics between excited NH₃ injection and its simulant gas

injection in 600°C and 700 °C. When NH₃ only inject to reaction field, NO_x removal reaction does not occur in this temperature range. However, when simulant gas (NH₃ + H₂) inject, NO_x removal reaction occurs in this temperature range. That is, it is evident that H₂ contribute to the expansion of Temperature window.

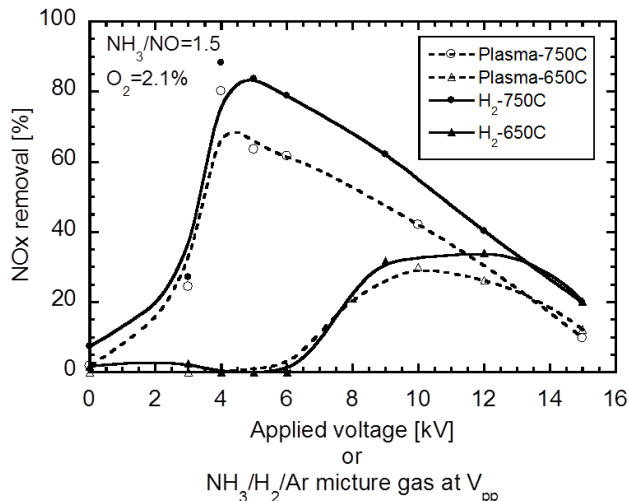


Fig.4 Comparison of deNO_x characteristics between excited NH₃ injection and its simulant gas injection.

IV. DISCUSSION

A. Inquest of NO_x removal mechanism

We goes through NO_x removal mechanism by excited NH₃ injection method with elementary process simulation because it has been found that chemical composition of excited NH₃ and contribution of H₂ to NO_x removal. Elementary process simulation is simulated using Miller & Bowman mechanism [7] and CHEMKIN-PRO (chemical reaction mechanism analysis software). Plug flow reactor is assumed as the reactor model. Concentrations of Various chemical species (N₂, O₂, NH₃, and H₂) are set as an initial condition.

Figure 5 shows simulation result of the contribution of H₂ to NO_x removal. As NH₃ coexists with H₂ in the reaction field, new reaction pathway(HNO → NH) occurs. It is suspected that NO reduction reaction by NH contributes to the expanding of Temperature window.

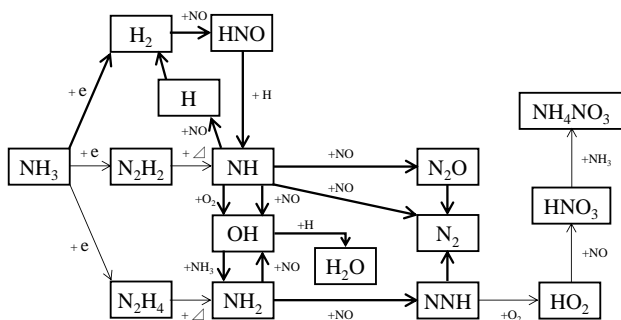


Fig.5 Comparison between elemental reaction analysis and experimental results.

V. CONCLUSION

It was shown that the Temperature window is 150-200 °C extended to the low-temperature side to inject excited NH₃ gas by atmospheric pressure plasma into the combustion exhaust gas. Excited NH₃ gas contains H₂ and unreacted NH₃ as a major ingredient. It was found to expand Temperature window when NH₃ inject with H₂. In NO_x removal reaction with excited NH₃, It was shown that H₂ contributes the expansion of Temperature window. It is suspected that NO reduction reaction by NH contributes to the expanding of Temperature window in deNO_x reaction field.

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